

Notice of References Cited	Application/Control No. 10/572,764		Applicant(s)/Patent Under Reexamination DESIMONE ET AL.	
	Examiner WILLIAM PHILLIP FLETCHER III		Art Unit 1717	Page 1 of 1

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*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	A	US-6,335,224 B1	01-2002	Peterson et al.	438/114
	B	US-			
	C	US-			
	D	US-			
	E	US-			
	F	US-			
	G	US-			
	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N	WO 2005/030822 A3	04-2005	WIPO	Desimone et al.	-----
	O					
	P					
	Q					
	R					
	S					
	I					

NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Rolland et al., "Solvent-Resistant Photocurable 'Liquid Teflon' for Microfluidic Device Fabrication," J. Am. Chem. Soc. 2004, 126, 2322-2323; published on web 02/06/2004.
	V	International Preliminary Examination Report for PCT/US2005/004421, 06/25/2008, 3 pages.
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	X	

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.